## Comment on "Distribution of Phase Slip in Charge-Density-Wave Conduction in NbSe<sub>3</sub>"

Recently, Gill [1] has reported measurements of phase slip in the charge-density-wave (CDW) conductor NbSe<sub>3</sub> which are suggested to be inconsistent with previous interpretations. Phase slip is required for conversion between CDW current and single-particle current at current contacts, and is driven by strain in the CDW. In a 1D model [2], this strain is produced by an excess voltage  $V_{\rm ps}$  dropped uniformly between current contacts. Significant phase slip occurs only within a length  $L_{\rm ps}$  of the current contacts, where the magnitude of the strain is largest.

Gill compared four-probe I-V measurements using the normal (N), transposed (T), and mixed (M) configurations, shown in Fig. 1(a). In terms of the measured current  $I_{\text{tot}}$ , voltage V, and low-field (single-particle) resistance  $R_s$ , the CDW current is defined as  $I_{CDW} \equiv I_{tot}$  $-V/R_s$ . If the phase slip voltage  $V_{ps}$  is dropped uniformly between current contacts, then at a given  $I_{CDW}$ there should be an excess voltage (and thus excess single-particle and total currents  $I_s$  and  $I_{tot}$ ) in each of these configurations, proportional to the fraction of the length between current contacts included between the voltage contacts. Since the inner contact pair separation used in Ref. [1] was much smaller than the outer contact pair separation, the voltages V and currents  $I_{\text{tot}}$  measured at fixed  $I_{CDW}$  in the N and M configurations should be comparable, and smaller than measured in the T configuration. Instead, Ref. [1] found a large difference between M and N, roughly one-third the difference between T and N. This difference was interpreted as evidence for an excess voltage drop near the current contacts within the length  $L_{ps}$  where phase slip occurs, and was used to calculate the magnitude of  $L_{ps}$  as a function of current and temperature.

The interpretation in Ref. [1] was based upon two assumptions: (1) that the voltage contacts were nonperturbing and (2) that the converted CDW current was simply shunted through the single-particle resistivity  $\rho_s$  in the phase slip region. Reference [1] used 30  $\mu$ m wide evaporated indium voltage contacts on a 2  $\mu$ m thick crystal. We have found that 5  $\mu$ m wide indium contacts shunt roughly 30% of the total current in 1  $\mu$ m thick crystals, so that the contacts used in Ref. [1] likely shunted nearly all the current. Below a shunting contact, the electric field is greatly reduced. Consequently, phase stress must accumulate on both sides of the voltage contact to provide enough force on the CDW to keep it moving in this field-reduced region. The mixed voltage thus contains an extra contribution to produce this stress.

To test the effects of field and stress perturbations by voltage contacts, we have performed mixed configuration measurements using both a completely nonperturbing contact (M1, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly perturbing conducting atomic force microscope tip) and a strongly perturbing contact <math>(M2, an electrically conducting atomic force microscope tip) and a strongly pe

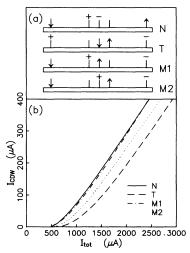


FIG. 1. (a) Four-probe measurement configurations discussed in the text and (b) CDW current  $I_{\text{CDW}}$  versus total current  $I_{\text{tot}}$  in NbSe<sub>3</sub> at T=100 K. The inner pair of contacts used in N and M 1 are 270  $\mu$ m apart; the inner pair used in M 2 are 230  $\mu$ m apart; the current contacts in M 1 are 4430  $\mu$ m apart; and the outermost pair of contacts are 8630  $\mu$ m apart.

silver paint, 40  $\mu$ m wide). As shown in Fig. 1(b), the perturbing contact gives results similar to those obtained in Ref. [1], while the nonperturbing contact gives results consistent with  $V_{\rm ps}$  being dropped uniformly between the current contacts. Thus, voltage contact perturbations were likely responsible for most of the effects reported in Ref. [1].

The general validity of the second assumption used in the analysis of Ref. [1] is also uncertain. Although there is at present no two-fluid theory for the phase slip process, it seems unlikely that the converted CDW electrons make no contribution to the total conductivity within  $L_{\rm ps}$ . Neglecting this contribution for the  $T_P=145$  K CDW in NbSe3 is reasonable because of the large single-particle density associated with ungapped portions of the Fermi surface. However, in fully gapped materials (e.g.,  $K_{0.3}$ -MoO3) at low temperatures, the single-particle density becomes vanishingly small, so the conductivity associated with converted CDW electrons may be significant.

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